

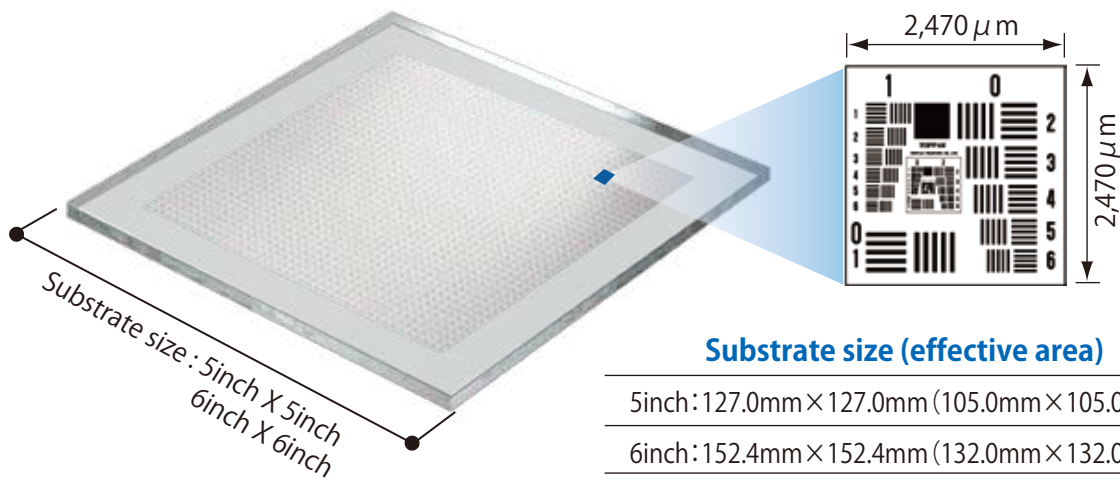
For precision management, the resolution confirmation of the device

TOPPAN TEST CHART

It is the photomask which formed the basic-shaped pattern with chromium on the high purity glass substrate.

We prepare for a positive type mask and a negative type mask.

It is available in the uses such as accuracy management of equipment, a resolution check, and a valuation basis at photoresist selection.

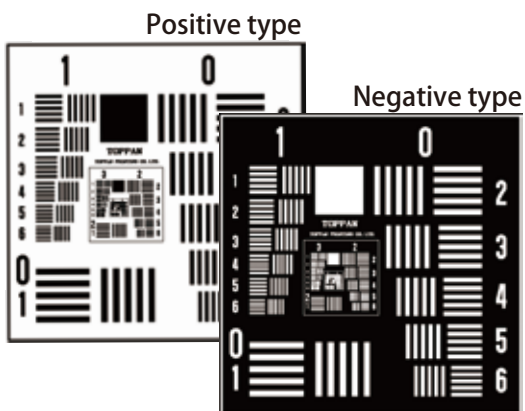


Substrate size (effective area)

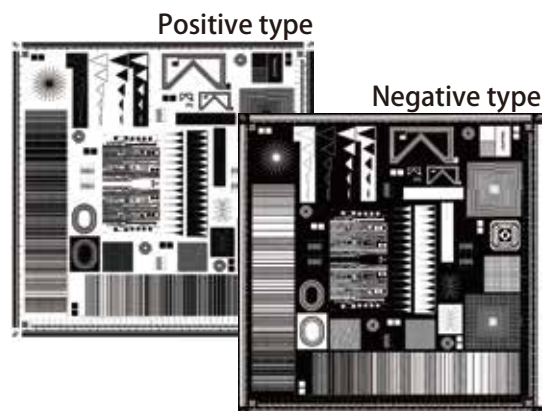
5inch : 127.0mm X 127.0mm (105.0mm X 105.0mm)

6inch : 152.4mm X 152.4mm (132.0mm X 132.0mm)

Pattern : No.1



Pattern : No.2



In addition to the above standard products, we can also produce custom models.

TOPPAN PHOTOMASK CO., LTD.

e-mail : photomask@toppan.co.jp